

INFORMATION DISCLOSURE CITATION
IN AN APPLICATION

MAR 03 2004

(so several sheets if necessary)

Document Number (Continuation)

HTIRC-02-015

Application Number

10/734,422

Applicant

Jeiwei Chang et al.

Filing Date

12/12/03

Group Art Unit

U. S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILED DATE IF APPROXIMATE
DCD	6496334	12/17/02	Pang et al.	360	319	5/26/00
DCD	6294101	9/25/01	Silverbrook	216	27	7/10/98
DCD	5627704	5/6/97	Lederman et al.	360	113	2/12/96
DCD	5668688	9/16/97	Dykes et al.	360	113	5/24/96

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Portion of Pages, Etc.)

DCD	-	Co-pending U.S. Patent HTIRC-02-014, "Method of Adjusting CoFe Free Layer Magnetostriiction", to M. Li et al., Serial No. 10/718,373, filed 11/20/03.

EXAMINER

/Daborah Chacko-Davis/

DATE CONSIDERED

05/11/2006

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.